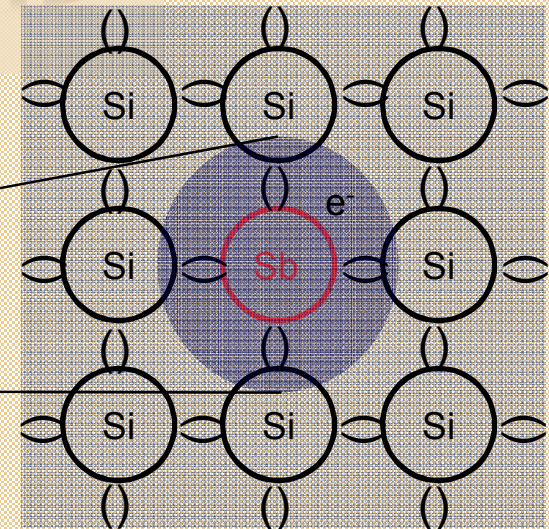
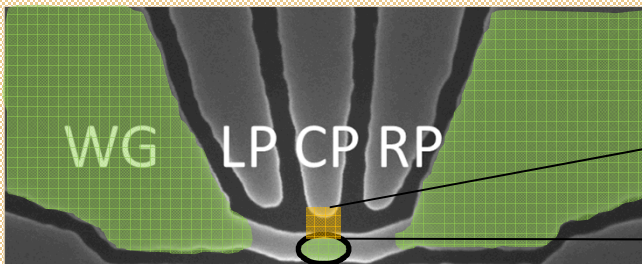


Silicon Quantum Dots with Counted Antimony Donor Implants



M. Singh, J. L. Pacheco, D. R. Luhman, E. S. Bielejec, M. P. Lilly and M. S. Carroll

This work was performed, in part, at the Center for Integrated Nanotechnologies, a U.S. DOE Office of Basic Energy Sciences user facility. The work was supported by Sandia National Laboratories Directed Research and Development Program. Sandia National Laboratories is a multi-program laboratory operated by Sandia Corporation, a Lockheed-Martin Company, for the U. S. Department of Energy under Contract No. DE-AC04-94AL85000.

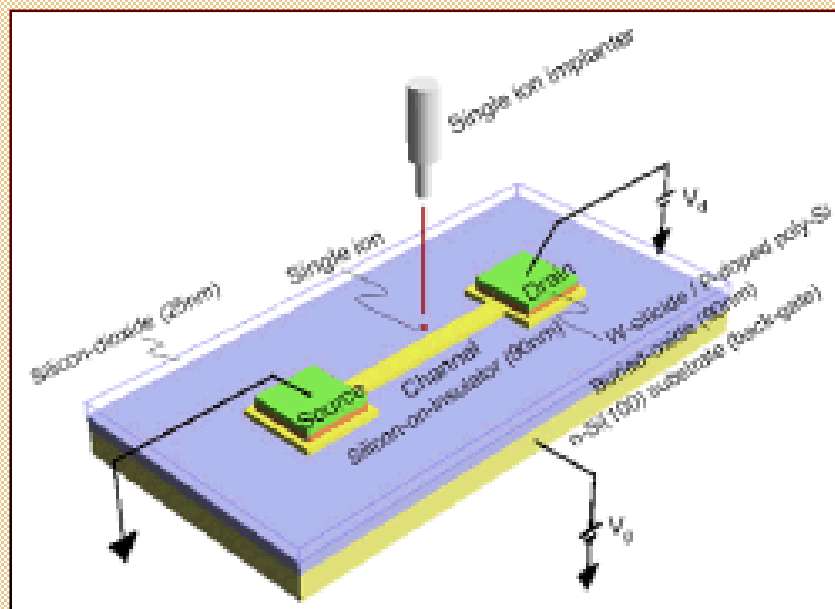
Why count donors?

Two qubit experiments require deterministic control over number of donors

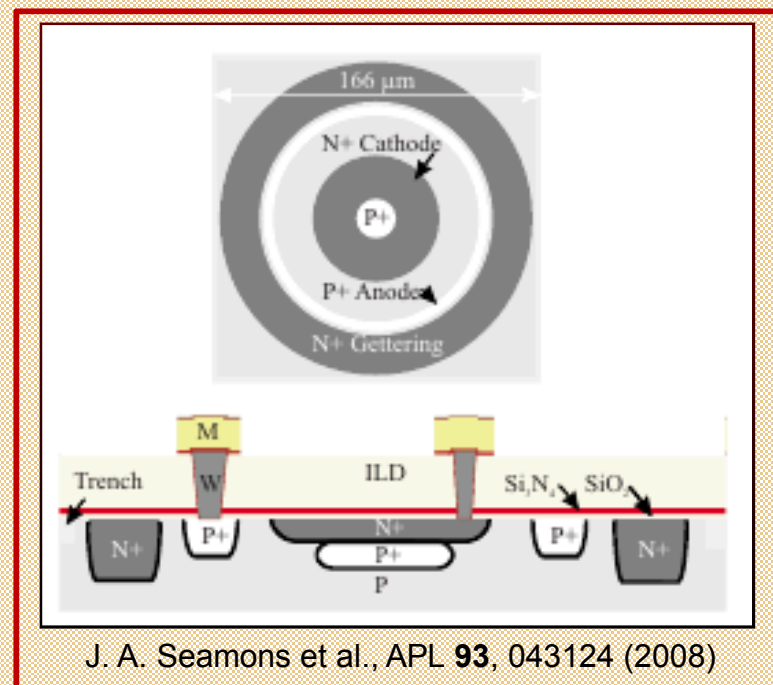


B.E. Kane, Nature **393**, 133 (1998)

How to count donors:



T. Shinada et al., Nanotechnology **19**, 345202 (2008)

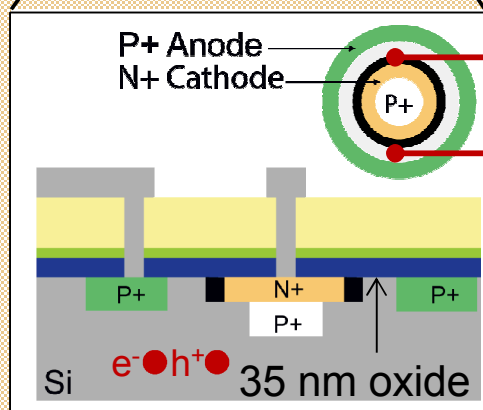
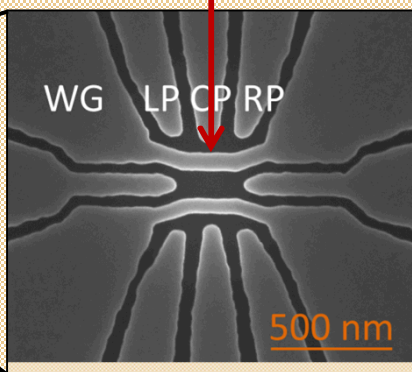
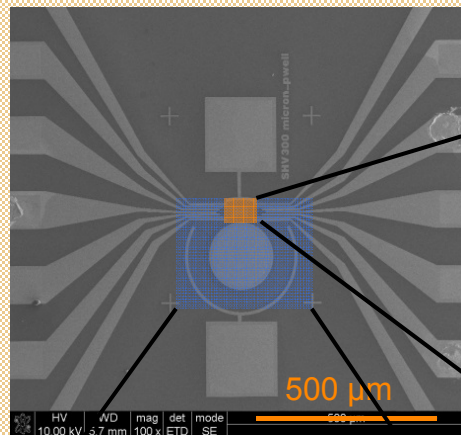


J. A. Seamons et al., APL **93**, 043124 (2008)



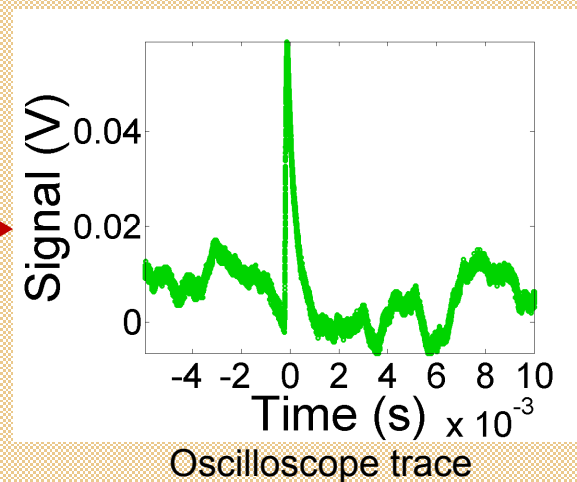
How do we count

120 keV Sb⁺



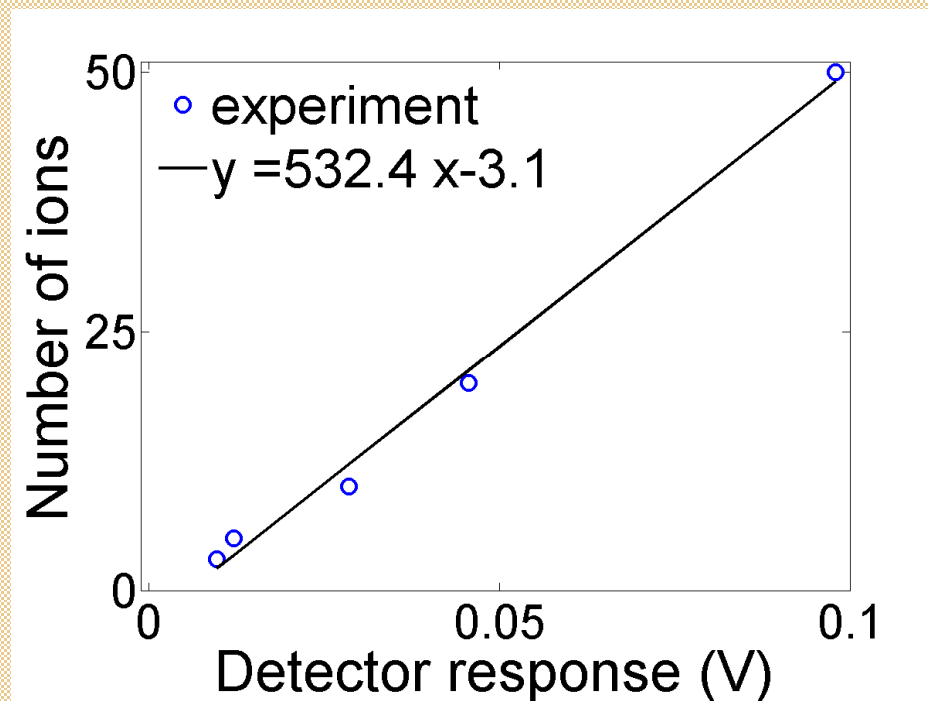
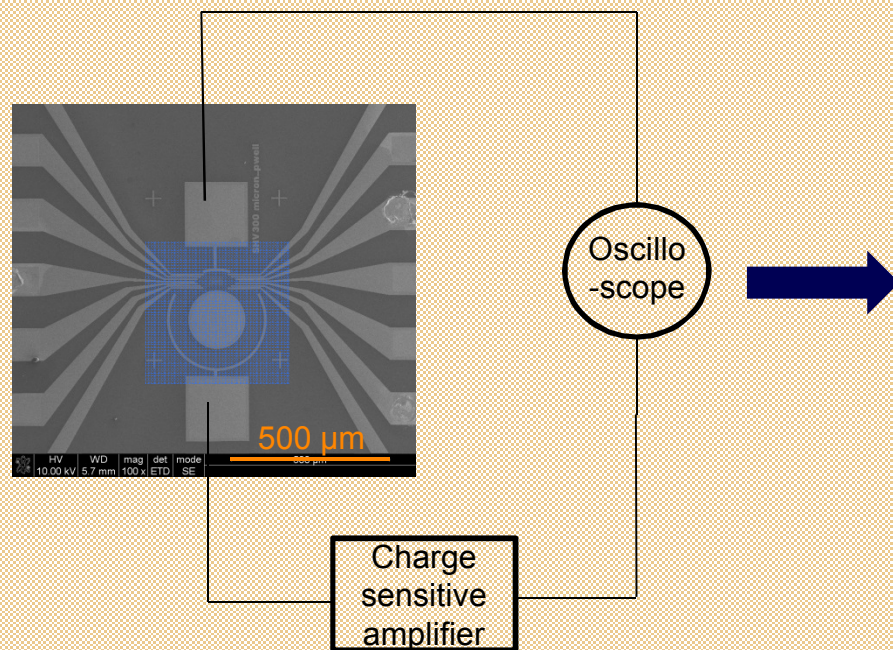
Ion beam induced charge (IBIC)

Charge
sensitive
amplifier

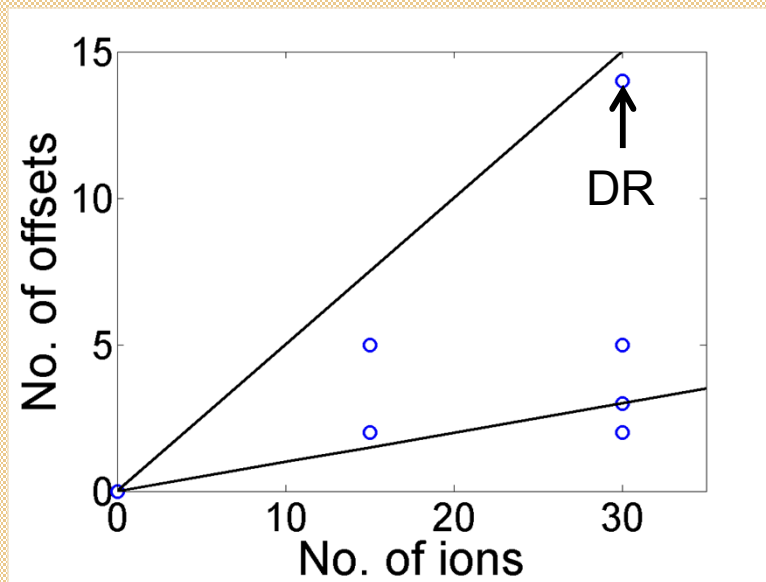
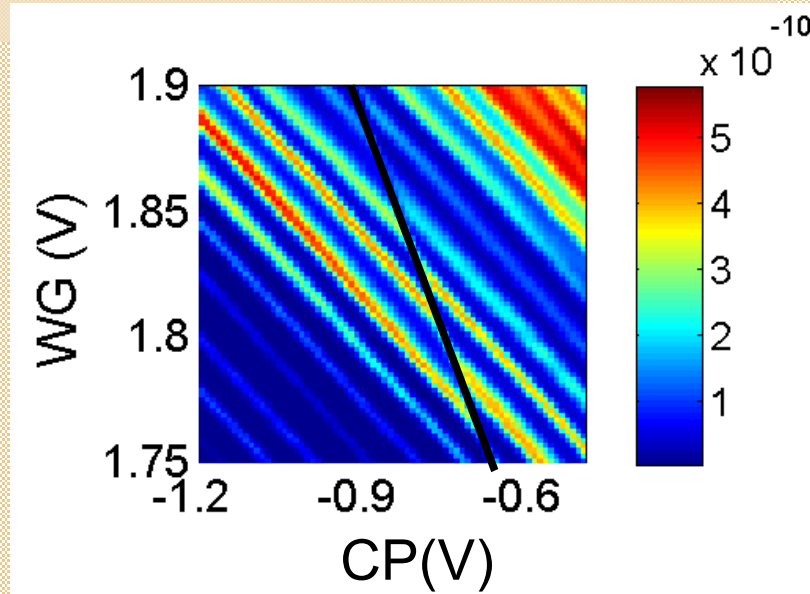
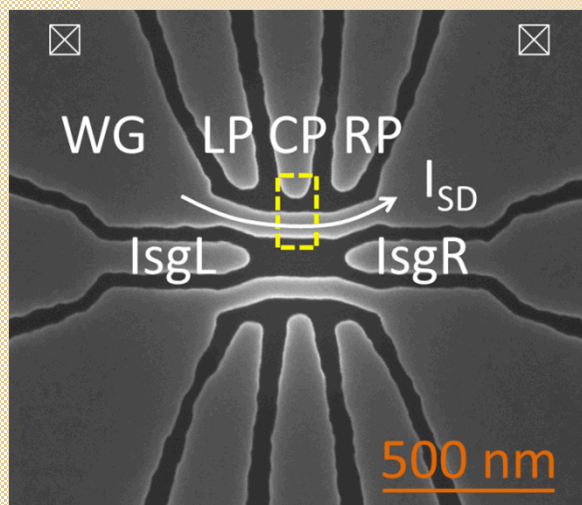


Making devices with counted no. of donors

Counting the ion implants

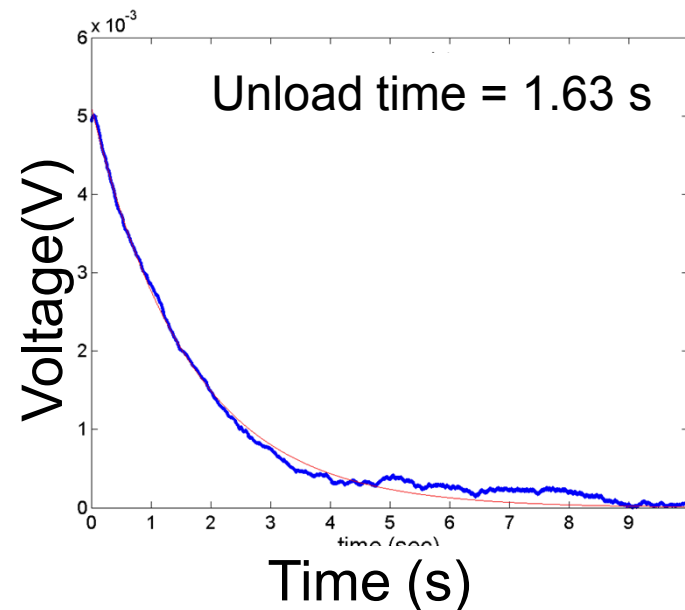
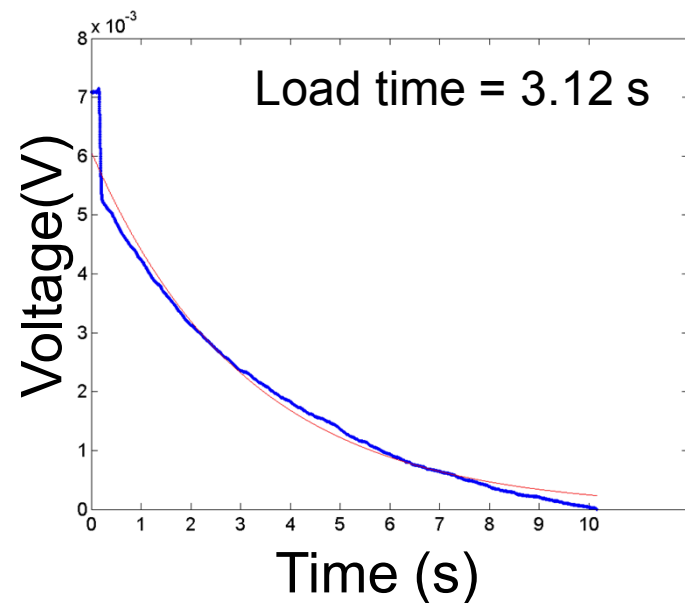
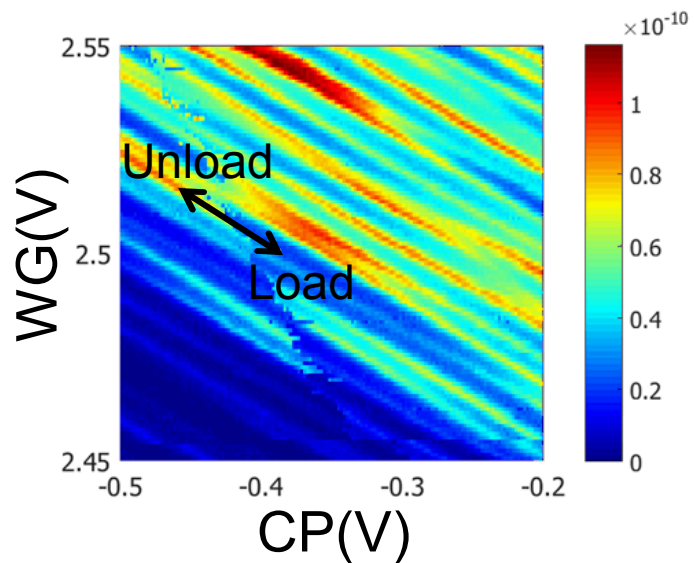


Does the SET work/see the donors?

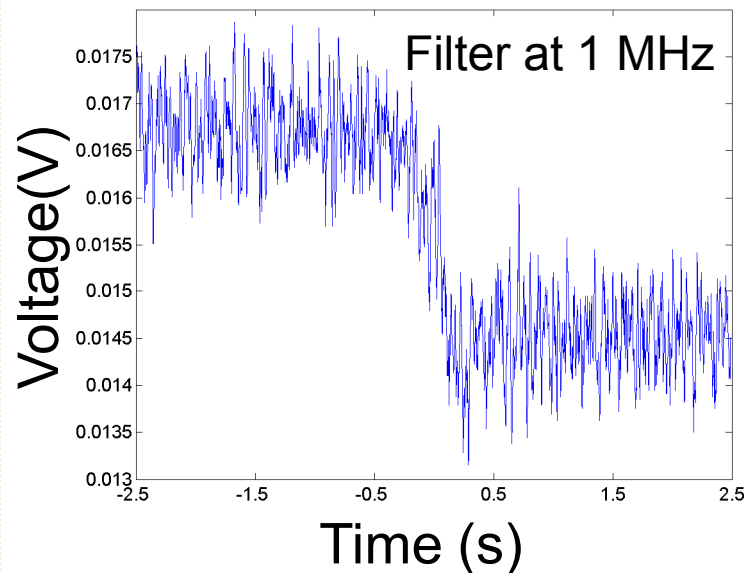
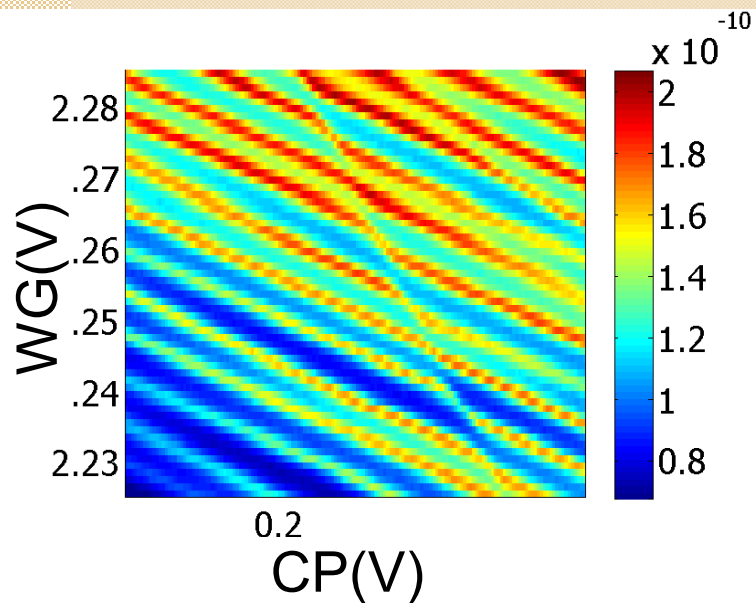


Tunneling Time Measurement on Counted Donors

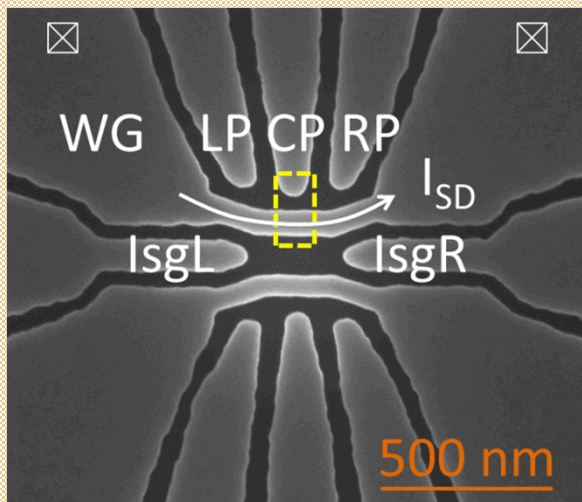
Some offsets are very slow



Tunneling Time Measurement on Counted Donors



Others are very fast

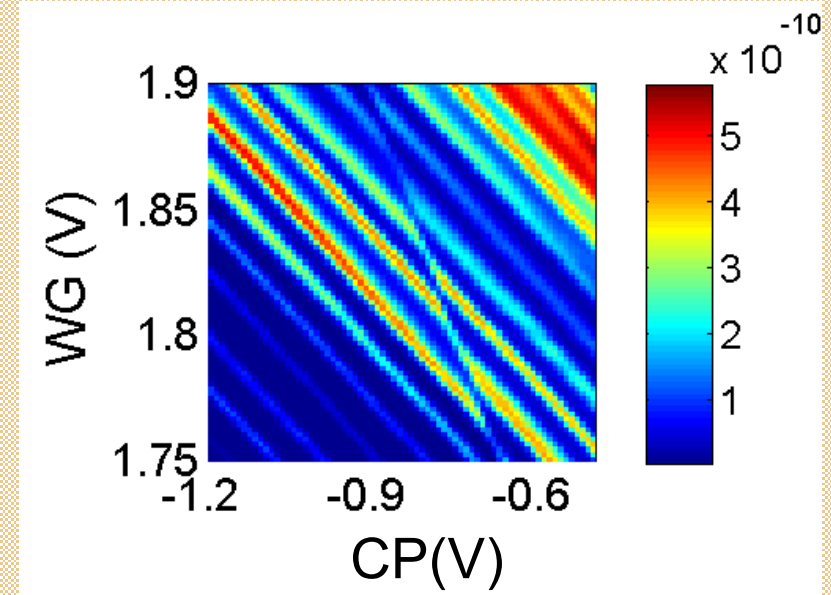
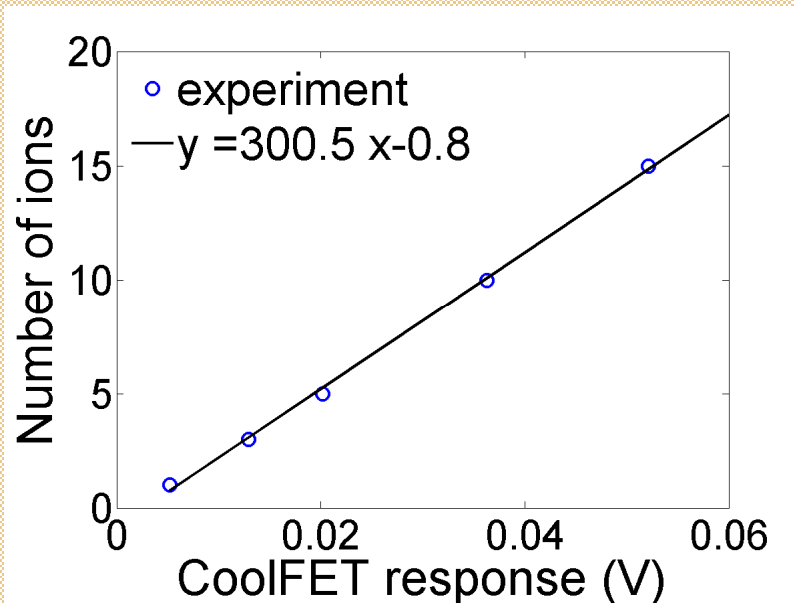


1. With focused ion beam system and lithography, we can control lateral position to ~ 10 nm
2. By thinning oxide to 7 nm in the implantation region, we can use lower energy ions and reduce depth straggle

Results

THIS WORK:

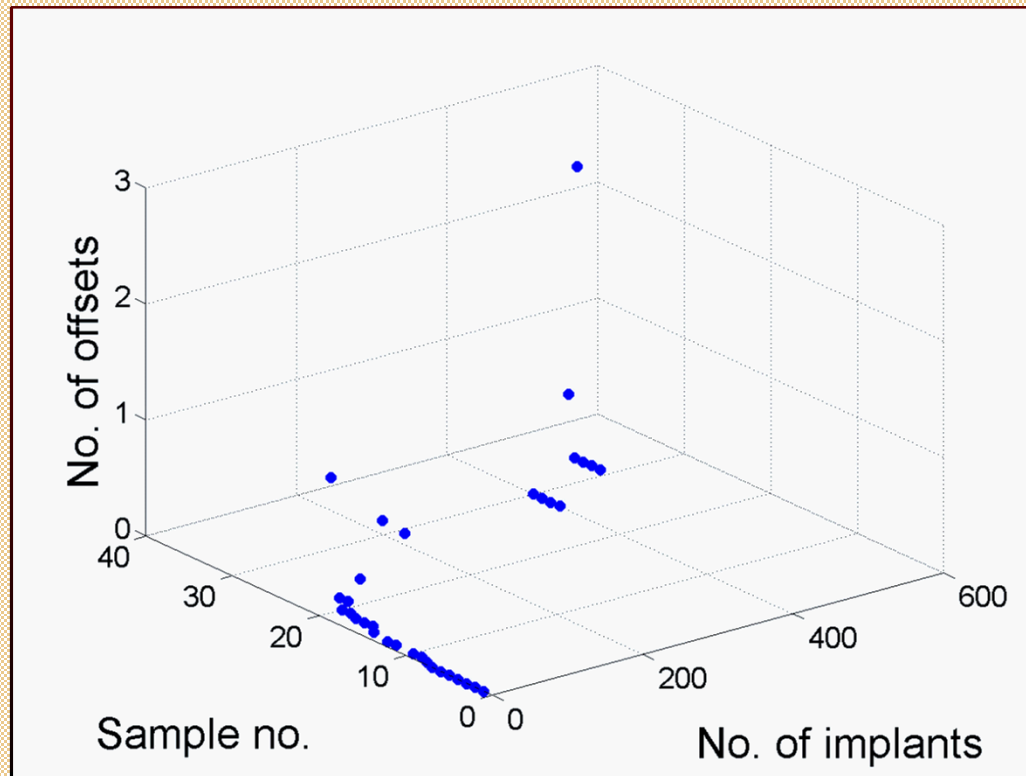
Correlation between no. of donors implanted and no. of charge offsets in transport measurement is seen (APL **108**, 6, 062101 (2016))



Thank you

Additional Information

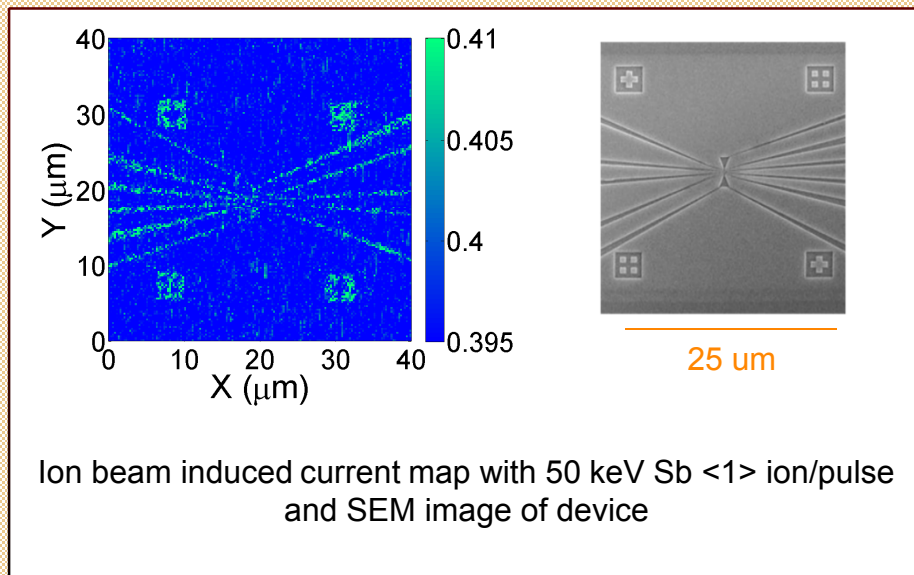
7 nm counted implants



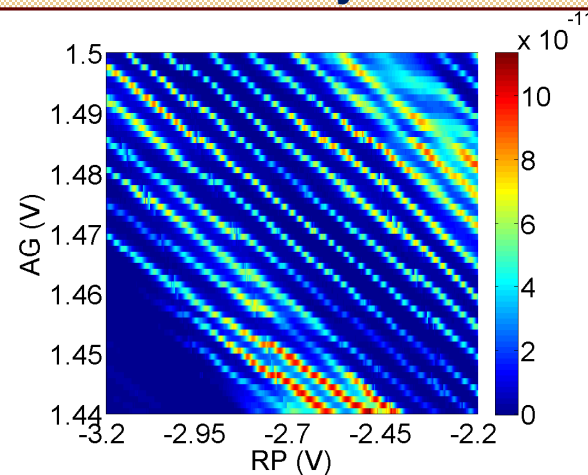


Single ion detection and functional SET

Single ion detection

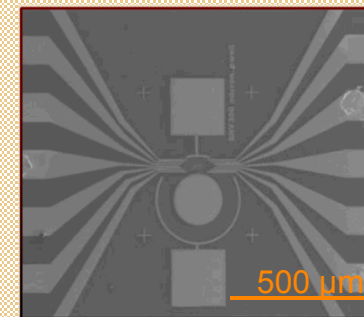


SET with capacitances agree with simulations of an electrostatically defined dot



$T = 25 \text{ mK}$, $C_{AG} = 26.7 \text{ aF}$, $C_{RP} = 1.6 \text{ aF}$, $C_{CP} = 2.2 \text{ aF}$, $C_{LP} = 1.4 \text{ aF}$

Diode detectors that can detect a single ion integrated with functional SETs.

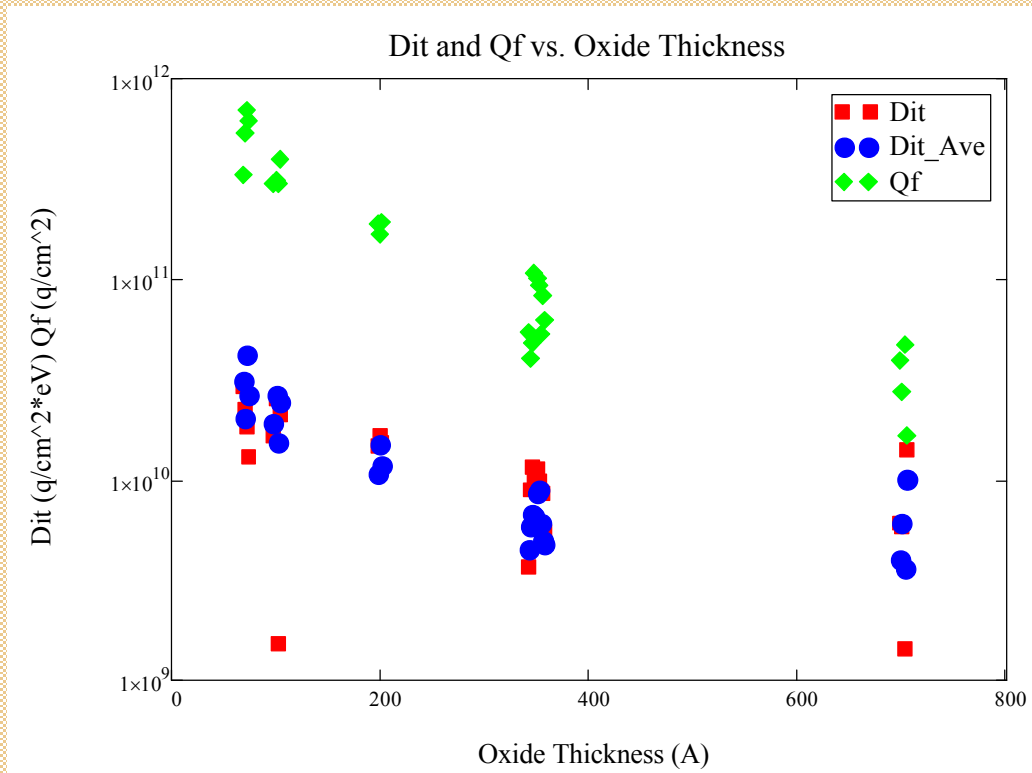


Sample Synthesis: 7 nm oxide

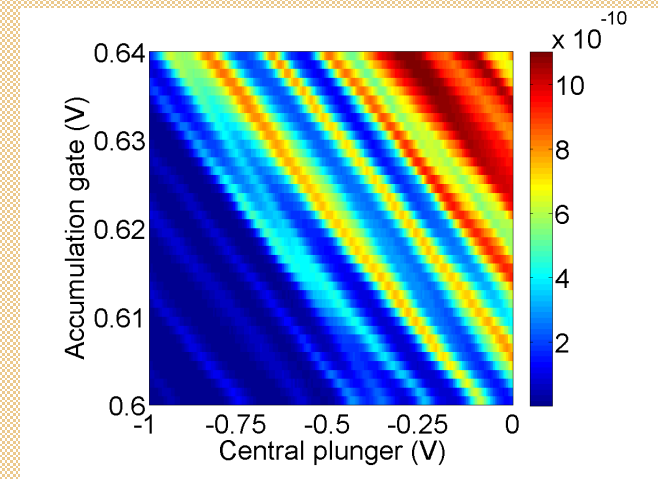
1. Interface trapped charge (D_{it}) and fixed charge (Q_f) are concerns for dots and donors near the SiO_2/Si interface
2. Thinner oxides lead to higher fixed charge

We require deterministic control over:

1. Placement of donors: needs thin oxide
2. Number of donors



However, we are able to obtain stable single dots in these systems



AuSiSb Mass Spectrum

